

Special Issue

Recent Advances in Chemical Process Safety

Message from the Guest Editors

This Special Issue on “Recent Advances in Chemical process Safety” seeks high-quality works focusing on the latest advances in chemical process safety, especially for the fluorine chemical industry. Topics include, but are not limited to:

- Evaluation of chemical process safety;
- Novel detection equipment and technology in corrosion and leakage;
- Fault detection and diagnosis;
- Risk management and control;
- Real-time monitoring and early warning as well as emergency rescue;

Guest Editors

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Deadline for manuscript submissions

closed (20 November 2021)



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About the Journal

Message from the Editor-in-Chief

You are invited to contribute either a research article or a comprehensive review for consideration and publication in *Processes* (ISSN 2227-9717). *Processes* is published in open access format – research articles, reviews, and other content are released on the internet immediately after acceptance. The scientific community and the general public have unlimited, free access to the content. As an open access journal, *Processes* is supported by the authors and their institutes through the payment of article processing charges (APCs) for accepted papers. We would be pleased to welcome you as one of our authors.

Editor-in-Chief

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